R¹ represents isobutyryl, tigloyl, isovaleryl, or 2-methylbutanoyl;



 R^2 represents a hydrogen atom, a benzoic acid residue having a substituent, a nicotine acid residue having a substituent, or a quinoxalinecarboxylic acid residue having a substituent, wherein the substituent is selected from the group consisting of hydroxyl, halogen atoms, nitro, amino, diC_{1-6} alkylamino, formylamino, C_{1-6} alkyl, C_{1-6} alkoxy, benzyloxy, C_{1-10} aliphatic acyloxy, benzyloxy, C_{1-4} alkyloxycarbonyloxy, C_{1-4} alkyloxycarbonyl (C_{1-4}) alkyloxy, p-nitrobenzyloxycarbonyl (C_{1-4}) alkyloxy, C_{1-6} alkylsulfonyloxy, C_{1-6} alkylphosphoryloxy, and diphenylphosphoryloxy, and

R³ represents a hydrogen atom.



- 3. (Amended) The compound or salt thereof according to claim 1, wherein R² is selected from the group consisting of a hydroxybenzoic acid residue, a nicotinic acid residue having a hydroxy substituent, and a quinoxalinecarboxylic acid residue having a hydroxy substituent.
- 12. (Twice Amended) A method for preventing the appearance and proliferation of fungi or exterminating fungi, comprising using an effective amount of the compound or salt thereof according to any one of claims 1, 20 or 21 for agricultural or garden plants.



- 13. (Twice Amended) A method for treating fungal infectious diseases, comprising administering an effective amount of the compound or salt thereof according to any one of claims 1, 20 or 21 to animals including human beings.
- 14. (Twice Amended) A method for treating fungal infectious diseases, comprising applying an effective amount of the compound or salt thereof according to any one of claims 1, 20 or 21 to agricultural or garden plants.
- 15. (Twice Amended) A method for preventing the appearance and proliferation of fungi or exterminating fungi, comprising applying an effective amount of the compound or salt thereof according to any one of claims 1, 20 or 21 to industrial products or in the course of production of industrial products.